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(54) **PHOTOSENSITIVE COMPOSITION,  
COMPOUND FOR USE IN THE  
PHOTOSENSITIVE COMPOSITION, AND  
PATTERN-FORMING METHOD USING THE  
PHOTOSENSITIVE COMPOSITION**

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This patent is subject to a terminal dis-  
claimer.

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(58) **Field of Classification Search** ..... None  
See application file for complete search history.

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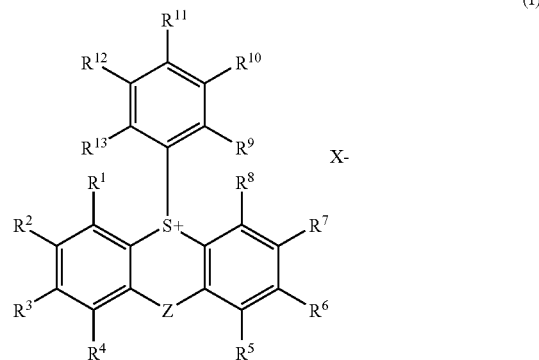
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(57) **ABSTRACT**

A photosensitive composition includes (A) a compound rep-  
resented by the following formula (I):



wherein R<sup>1</sup> to R<sup>13</sup> each independently represents a hydrogen  
atom or a substituent, Z represents a single bond or a divalent  
linking group, and X<sup>-</sup> represents an anion containing a proton  
acceptor functional group.

**16 Claims, 1 Drawing Sheet**